## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	William F. Seng, et al.	)
Serial No.:	ТВА	) ) Examiner: TBD
Filed:	Filed Herewith	) Art Unit: TBD
For:	LOW-TEMPERATURE, LONG TERM ANNEALING OF NICKEL CONTACTS TO LOWER INTERFACIAL RESISTANCE	) ) ) ) )

## INFORMATION DISCLOSURE STATEMENT

Mail Stop Patent Application Commissioner of Patents P.O. Box 1450 Alexandria, VA 22202

Dear Sir:

Pursuant to 37 CFR §1.97 - §1.98, Applicants hereby bring to the attention of the United States Patent and Trademark Office, the references listed on the attached Form PTO-1449.

Respectfully submitted,

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Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Application Number	TBA	
INFORMATION DISCLOSURE				Filing Date	Filed Herewith	
STATEMENT BY APPLICANT			PPI ICANT	First Named Inventor	William F. Seng	
OTATEMENT BY ALLEGAN				Art Unit	TBD	
(use as many sheets as necessary)			necessary)	Examiner Name	TBD	
Sheet	1	of	1	Attorney Docket Number	90065.001090/8018.00	

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.1	publisher, city and/or country where published.			
	1	"Interface Chemistry and Electrical Properties of Annealed Ni and Ni/Al-6H SiC Structures", C. Halling, R. Yakimova, V. Krastev, Ts. Marinova and E. Janzen, Inst. Phys. Conf. Seri No. 196, 1996 IOP Publishing Ltd.			
	2	"The Influence of Dry Cleaning Techniques on Thermal Oxides Grown on 4H and 6H P-type SiC", CM. Zetterling, C.I. Harris, M. Ostling and V.V. Afanas'ev", Inst. Phys. Conf. Seri No. 196, 1996 IOP Publishing Ltd.			
	3	"Specific Contact Resistance as a Function of Doping N-type 4H and 6H-SiC", Inst. Phys. Conf. Seri No. 196, 1996 IOP Publishing Ltd.			
	4	"Aluminum Doped 6H SiC: CVD Growth and Formation of Ohmic Contacts", Inst. Phys. Conf. Seri No. 196, 1996 IOP Publishing Ltd.			
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<u>.</u>					
Examiner Signature	- 1	Date Considered			

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not

<sup>&</sup>lt;sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached. This collection of information is required by 37 CFR 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 120 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.